

# Resource Summary Report

Generated by [Kravitz](#) on Sep 10, 2026

## Kloe: UV-KUB 2 - UV-LED masking system

RRID:SCR\_021141

Type: Tool

### Proper Citation

Kloe: UV-KUB 2 - UV-LED masking system (RRID:SCR\_021141)

### Resource Information

**URL:** <https://www.kloe-france.com/en/laser-lithography/photolithography-systems/uv-exposure/uv-kub-2>

**Proper Citation:** Kloe: UV-KUB 2 - UV-LED masking system (RRID:SCR\_021141)

**Description:** Compact exposure masking system is UV-LED masking system equipped with LED based optical head, collimated and homogeneous. One level mask aligner. Its masking function enables to reach resolutions less than 1um. This system is compatible with any of photoresists such as AZ series, Shipley series, SU-8 and K-CL series.

**Synonyms:** UV?KUB 2 masking system, UV-KUB 2

**Resource Type:** instrument resource

**Keywords:** KLOE SA, UV LED masker, exposure masking system, instrument, equipment, USEDit

**Resource Name:** Kloe: UV-KUB 2 - UV-LED masking system

**Resource ID:** SCR\_021141

**Alternate IDs:** Model\_Number\_UV-KUB 2

**Record Creation Time:** 20220129T080354+0000

**Record Last Update:** 20260905T132935+0000

### Ratings and Alerts

No rating or validation information has been found for Kloe: UV-KUB 2 - UV-LED masking system.

No alerts have been found for Kloe: UV-KUB 2 - UV-LED masking system.

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## Data and Source Information

**Source:** [SciCrunch Registry](#)

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## Usage and Citation Metrics

We have not found any literature mentions for this resource.